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( 140 / ²)

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[8] ( ).

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Coaxial Energetic Ion Deposition Process,  
Alameda Applied Sciences Corporation (2235 Polvorosa Avenue, Suite 230 San  
Leandro, CA 94577),

Coaxial Energetic Ion  
Deposition Process.

Benet Laboratories (Watervliet Arsenal, Watervliet NY 12189-  
4050),

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